

Planarization of Transferred Wafer-scaled CVD-Graphene

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Abstract

The wet chemical method is the most popular way to transfer CVD-grown graphene from the metal growth substrate because of its simplicity and amenability. However, the quality of transferred graphene still needs to be optimized since wrinkles appear during the process of transfer which strongly influences the physicochemical properties of the graphene samples. Here, we report a new approach, "Transferred Graphene Planarization Method", which can significantly reduce large-scale wrinkles in transferred graphene by spinning the samples in different rotation rates. The surface morphology of the samples fabricated with and without the process of this method was inspected by the atomic force microscopy (AFM), respectively. Therefore, our work suggests an effective route for producing transferred graphene with higher quality and flatter surface.

References

[1] Authors, Journal, **Issue** (Year) page.

Figures